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Alford et al.

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(54) **ASPIRATING PHOTOCHEMICAL ODOR CONTROL SYSTEM FOR WASTEWATER LIFT STATION AND FORCE MAIN ODORS**

C02F 2209/265; C02F 2209/235; C02F 2303/02

See application file for complete search history.

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A61L 9/20 (2006.01)

(52) **U.S. Cl.**
CPC **A61L 9/205** (2013.01)

(58) **Field of Classification Search**
CPC A61L 9/205; A61L 9/20; B01D 53/46;

(57) **ABSTRACT**

An aspirating photochemical odor control system allows odoriferous gases to reside in a wet well or force main (odor source) until gas pressure in the odor source forces the gases out. A check valve admits air into the odor source when pressure in the odor source decreases appreciably below ambient pressure. When pressure in the odor source exceeds ambient pressure, a check valve permits flow of gases from the odor source to a photochemical reaction chamber and solar thermal collector to react with oxidizer generated by UV lamps, before being exhausted to the atmosphere.

20 Claims, 5 Drawing Sheets

